

[LITHOGRAPHY PROCESS]

Abstract of Disclosure

A lithography process. A substrate is provided first. Then a protective layer is formed on the substrate and a patterned photoresist layer is formed on a surface of the protective layer. A normal lithography process is executed. Finally a first inspection process is performed to screen the correctness of the patterned photoresist layer. When the correctness of the patterned photoresist layer does not fulfill the spec, the patterned photoresist layer on the surface of the protective layer is thereafter removed and the patterned photoresist layer is reformed on the surface of the protective layer.

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